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**JUN 14 2005**

**PATENT  
CH920010003US1**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of Applicants:

Date: January 17, 2005

Bietsch, et al.

Group Art Unit: 1751

Serial No.: 10/081,860

Examiner: Lynette T Umez Eronini

Filed: February 22, 2002

Docket No.: CH920010003US1

For: *SELECTIVE ETCHING OF SUBSTRATES WITH CONTROL OF THE ETCH PROFILE*

Assistant Commissioner for Patents  
Post Office Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the Official Action dated May 2, 2005, please amend the above-identified application as set forth in the Appendix attached hereto.

**IN THE CLAIMS:**

Cancel all Claims except for Claim 1 which now embodies the substance of Claims 11 and 12.

**REMARKS**

It is submitted that the claims as amended in the instant response will place the claims in condition for allowance.